Even though the mechanical stage used to position the substrate can be very accurate (positioning error of ≈20 nm or less), field-stitching errors occur, causing underexposures or overexposures that manifest themselves, after development of the resist, as increases or decreases in grating thickness along the field boundaries. Because all the fields are of the same size, the stitching errors form another grating that has a period equal to the field size. Hence, the light scattered from the field boundaries adds coherently: this is ghost diffraction.

The modified scheme for electron-beam writing is based on the concept of reducing the degree of periodicity of the stitching errors. In this scheme, the overall grating area is divided into sub-areas within which the grating patterns are written in differently sized fields. For a typical convex or concave grating, the sub-areas are most easily defined as annular areas that correspond to equal-height slices through the substrate (see figure). Hence, the grating pattern in each annulus is written with a different field size.

The ghost order intensities are proportional to the square of the scattering amplitudes. Hence, if \( N \) different field sizes are used, the intensity of ghost diffraction can be expected to be reduced to approximately \( N^{-2} \) times the intensity obtained with a single field size.

To test this concept, two nominally identical gratings were fabricated. The pattern of the first grating was written by stitching together fields of the same size over its entire area, while the pattern of the second grating was established by use of four different field sizes. Whereas the ghost diffraction from the first grating was clearly noticeable, the intensity of ghost diffraction from the second grating was so low as to be undetectable against the diffuse-scattering background.

This work was done by Daniel Wilson and Johan Backlund of Caltech for NASA’s Jet Propulsion Laboratory. Further information is contained in a TSP (see page 1).

In accordance with Public Law 96-517, the contractor has elected to retain title to this invention. Inquiries concerning rights for its commercial use should be addressed to: Innovative Technology Assets Management JPL Mail Stop 202-233 4800 Oak Grove Drive Pasadena, CA 91109-8099 (818) 354-2240 E-mail: iaoffice@jpl.nasa.gov Refer to NPO-41302, volume and number of this NASA Tech Briefs issue, and the page number.

**Target-Tracking Camera for a Metrology System**

**Angular measurements are updated at a rate of hundreds of hertz.**

*NASA’s Jet Propulsion Laboratory, Pasadena, California*

An analog electronic camera that is part of a metrology system measures the varying direction to a light-emitting diode that serves as a bright point target. In the original application for which the camera was developed, the metrological system is used to determine the varying relative positions of radiating elements of an airborne synthetic-aperture-radar (SAR) antenna as the airplane flexes during flight; precise knowledge of the relative positions as a function of time is needed for processing SAR readings.

It has been common metrology system practice to measure the varying direction to a bright target by use of an electronic camera of the charge-coupled-device or active-pixel-sensor type. A major disadvantage of this practice arises from the necessity of reading out and digitizing the outputs from a large number of pixels and processing the resulting digital values in a computer to determine the centroid of a target: Because of the time taken by the readout, digitization, and computation, the update rate is limited to tens of hertz. In contrast, the analog nature of the present camera makes it possible to achieve an update rate of
hundreds of hertz, and no computer is needed to determine the centroid.

The camera is based on a position-sensitive detector (PSD), which is a rectangular photodiode with output contacts at opposite ends. PSDs are usually used in triangulation for measuring small distances. PSDs are manufactured in both one- and two-dimensional versions.

Because it is very difficult to calibrate two-dimensional PSDs accurately, the focal-plane sensors used in this camera are two orthogonally mounted one-dimensional PSDs. The camera also includes a beam splitter and two cylindrical lenses to focus line images of the target onto the PSDs — more specifically, to form a horizontal line image on the vertically oriented PSD and a vertical line image on the horizontally oriented PSD. The outputs from both ends of each PSD are processed by analog circuitry (see figure) to obtain an analog signal proportional to the displacement of the image centroid from the mid-length position along the PSD. The direction-measuring error of the readout has been found to be no more than 1/2,700 of the angular width of the field of view.

This work was done by Carl Liebe, Randall Bartman, Jacob Chapsky, Alexander Abramowici, and David Brown of Caltech for NASA’s Jet Propulsion Laboratory. Further information is contained in a TSP (see page 1). NPO-41466

Polarimetric Imaging Using Two Photoelastic Modulators

The frame rate is the difference between the resonance frequencies of the modulators.

NASA’s Jet Propulsion Laboratory, Pasadena, California

A method of polarimetric imaging, now undergoing development, involves the use of two photoelastic modulators in series, driven at equal amplitude but at different frequencies. The net effect on a beam of light is to cause (1) the direction of its polarization to rotate at the average of two excitation frequencies and (2) the amplitude of its polarization to be modulated at the beat frequency (the difference between the two excitation frequencies). The resulting modulated optical light beam is made to pass through a polarizing filter and is detected at the beat frequency, which can be chosen to equal the frame rate of an electronic camera or the rate of sampling the outputs of photodetectors in an array.

The method was conceived to satisfy a need to perform highly accurate polarimetric imaging, without cross-talk between polarization channels, at frame rates of the order of tens of hertz. The use of electro-optical modulators is necessitated by a need to obtain accuracy greater than that attainable by use of static polarizing filters over separate fixed detectors. For imaging, photoelastic modulators are preferable to such other electro-optical modulators as Kerr cells and Pockels cells in that photoelastic modulators operate at lower voltages, have greater angular acceptances, and are easier to use. Prior to the conception of the present method, polarimetric imaging at frame rates of tens of hertz using photoelastic modulators was not possible because the resonance frequencies of photoelastic modulators usually lie in the range from about 20 to about 100 kHz.

It is conventional to characterize the polarimetric state of incident light in terms of the Stokes vector \( (I, Q, U, V) \), where \( I \) represents the total intensity; \( Q \) represents the excess of intensity of light polarized at an angle designated as 0° over that of light polarized at a relative angle of 90°; \( U \) represents similarly the excess of intensity at 45° over that 135°, and \( V \) represents the excess of intensity of right circular polarization over left circular polarization. It has been shown theoretically that in the present method, there should be no cross-talk between the \( Q \) and \( U \) channels and that it should be possible to obtain the ratio \( U/I \) from two readings of a single photodetector taken when the polarizer is in two orientations that differ by 45°.

The figure schematically depicts a laboratory setup that was used to demonstrate the feasibility of the method. A collimated beam of white light was partially polarized by a glass plate at an oblique angle. The degree of polarization could be changed by rotating the glass plate. The light then passed through a circular-polarization subsystem that included (1) two photoelastic modulators having their fast axes at an angle of 0°, sandwiched between (2) two quarter-wave retarders oriented at angles of 45° and 135°, respectively. The two photoelastic modulators had resonance frequencies of about 42 kHz, differing by a beat frequency of about 9 Hz. The modulated light was then made to pass through a 0° or 45° polarizer on the way to a photodetector. A band-pass filter having a nominal pass wavelength of 672 nm with 20-nm bandwidth was mounted between the polarizer and the photodetector. Results of several experiments at various degrees of linear polarization were found to agree substantially with theoretical predictions.

This work was done by Yu Wang, Thomas Cunningham, David Diner, Edgar Davis, Chao Sun, Bruce Hancock, Gary Gutt, Jason Zan, and Nasrat Raouf of Caltech for NASA’s Jet Propulsion Laboratory. Further information is contained in a TSP (see page 1). NPO-43806